

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	22	semiconductor with (scrubb\$3 or rubb\$3 or clean\$3 or dipp\$3) with ((sodium adj hydroxide) or (sulfinic adj acid))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 13:44
L2	1	semiconductor with (scrubb\$3 or rubb\$3) with ((sodium adj hydroxide) or (sulfinic adj acid))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 13:45
L3	0	semiconductor with (scrubb\$3 or rubb\$3 or clean\$3 or dipp\$3) with (sulfinic adj acid)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:03
L4	8	semiconductor with (scrubb\$3 or rubb\$3 or clean\$3 or dipp\$3) and (sulfinic adj acid)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:03
L5	383	semiconductor and (scrubb\$3 or rubb\$3) and (sulfinic adj acid)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:07
L6	85	wafer and (scrubb\$3 or rubb\$3) and (sulfinic adj acid)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:08
L7	0	wafer and (scrubb\$3 or rubb\$3) and (adipic adj acid adj di\$2 \$ethylhexyl adj ester)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:11

L8	1	(scrubb\$3 or rubb\$3 and clean\$3) and (adipic adj acid adj di\$2 \$ethylhexyl adj ester)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/22 14:12
S1	2	("5387545" "5851906").PN.	US-PGPUB; USPAT	OR	ON	2007/07/01 16:27
S2	2	silicon and (native with oxide with removal with scrubbing)	USPAT	OR	ON	2007/07/01 16:32
S3	592	electromagnetic with dop\$3	USPAT	OR	ON	2007/07/02 10:49
S4	0	S3 and (energy with (Kj or kilojoule))	USPAT	OR	ON	2007/07/01 16:33
S5	0	S3 and (energy with (Kj or kilo\$joule))	USPAT	OR	ON	2007/07/01 16:33
S6	10	S3 and (energy with joule)	USPAT	OR	ON	2007/07/01 16:33
S7	3	S3 and (binding with energy)	USPAT	OR	ON	2007/07/01 16:36
S8	21	(electromagnetic with dop\$3) and energy and joule	USPAT	OR	ON	2007/07/02 10:51
S9	0	electromagnetic adj dop \$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/02 10:52
S10	0	electromagnetic adj wave adj dop\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/02 10:52
S11	238	(electromagnetic adj wave) with dop\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/02 16:30
S12	217	438/535.ccls.	US-PGPUB; USPAT	OR	ON	2007/07/02 16:32
S13	6	S12 and (native with oxide)	US-PGPUB; USPAT	OR	ON	2007/07/02 16:32
S14	6	("5599735").URPN.	USPAT	OR	ON	2007/07/02 16:55

S15	2597	((gas with phase with dop\$3) or GPD)	USPAT	OR	ON	2007/07/02 16:55
S16	250	gas adj phase adj dop \$3	USPAT	OR	ON	2007/07/02 16:56
S17	43	S16 and (native with oxide)	USPAT	OR	ON	2007/07/02 16:56
S18	217	438/535.ccls.	US-PGPUB; USPAT	OR	ON	2007/07/03 17:58
S19	2	semiconductor and (dip \$4 with cleann\$3 with solution)	USPAT	OR	ON	2007/12/19 11:40
S20	43	semiconductor with (scrubb\$3 or rubb\$3 or polish\$3) with ((sodium adj hydroxide) or (sulfinic adj acid) or (adipic adj acid))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/21 17:24
S21	25	semiconductor with (scrubb\$3 or rubb\$3 or clean\$3 or dipp\$3) with ((sodium adj hydroxide) or (sulfinic adj acid) or (adipic adj acid))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/21 17:28

5/22/08 2:26:33 PM

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